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International application number: PCT/GB05/001709

International filing date: 04 May 2005 (04.05.2005)

Document type: Certified copy of priority document

Document details: Country/Office: US

Number: 60/652,673

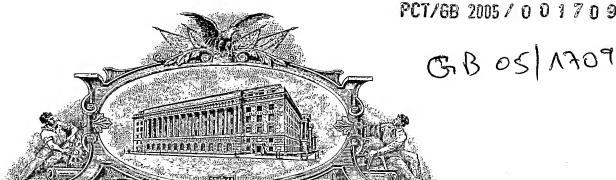
Filing date: 14 February 2005 (14.02.2005)

Date of receipt at the International Bureau: 31 May 2005 (31.05.2005)

Remark: Priority document submitted or transmitted to the International Bureau in

compliance with Rule 17.1(a) or (b)





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UNITED STATES DEPARTMENT OF COMMERCE

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**April 04, 2005** 

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APPLICATION NUMBER: 60/652,673

FILING DATE: February 14, 2005

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#### This is a request for filing a PROVISIONAL APPLICATION FOR PATENT under 37 CFR 1.53(c). INVENTOR(S) Residence Given Name (first and middle [if any]) Family Name or Surname (City and either State or Foreign Country) John Fleming WALKER United Kingdom Additional inventors are being named on the separately numbered sheets attached hereto TITLE OF THE INVENTION (280 characters max) CHIP SHIELDING SYSTEM AND METHOD Direct all correspondence to: **CORRESPONDENCE ADDRESS Customer Number** 24628 Place Customer Number Bar Code Label here OR Type Customer Number here Firm or L. Friedman Individual Name Address Welsh & Katz, Ltd. 120 S. Riverside Plaza, 22nd Floor Address City Chicago State Illinois ZIP 60606 Country USA Telephone 312-655-1500 Fax 312-65501501 **ENCLOSED APPLICATION PARTS (check all that apply)** Specification Number of Pages CD(s), Number Drawing(s) Number of Sheets 2 Other (specify) Cert. Exp. Mail EV555563702US; Return Receipt Postcard Application Data Sheet. See 37 CFR 1.76 Total # of sheets Application Size Fee \$0.00 METHOD OF PAYMENT OF FILING FEES FOR THIS PROVISIONAL APPLICATION FOR PATENT (check one) A check or money order is enclosed to cover the filing fees **FILING FEE** AMOUNT (\$) The Director is hereby authorized to charge filing fees or credit any overpayment to Deposit Account Number: \$200.00 23-0920 Payment by credit card. Form PTO-2038 is attached. The invention was made by an agency of the United States Government or under a contract with an agency of the United States Government. Yes, the name of the U.S. Government agency and the Government contract number are: Respectfully submitted, 14 February 2005 Date SIGNATURE REGISTRATION NO. [ 37,135

USE ONLY FOR FILING A PROVISIONAL APPLICATION FOR PATENT

(if appropriate)

Docket Number:

This collection of information is required by 37 CFR 1.51. The information is used by the public to file (and by the PTO to process) a provisional application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 8 hours to complete, including gathering, preparing, and submitting the complete provisional application to the PTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450. 1450, Alexandria, VA 22313-1450.

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P19LARGE/REV07

7251/93801

L. Friedman

312-655-1500

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Effective on 12/08/2004.			Complete if Known							
Fees pursuant to the Consolidated Appropriatons Act, 2005 (H.R. 4818).			Application Number							
FEE TRANSMITTAL			Filing Date 14 Februa			ary 2005				
for FY 2005			First Named Inventor WALKER							
			Examiner Name	Э						
Applicant claims small entity status. See 37 CFR 1.27			Art Unit							
TOTAL AMOUNT OF PAYMENT (\$) \$200.00			Attorney Docke							
METHOD OF PAYMENT (check all that apply)										
Check Credit Card Money Order None Other (please identify):										
Deposit Deposit Account Number: 23-0920 Deposit Account Name: Welsh & Katz, Ltd.										
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Charge fee(s) indicated below Charge fee(s) indicated below, except for the filing fee										
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1. BASIC FILING,										
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Application Type	Fee (\$)	Fee (\$)	Fee (\$			Fee (\$)	Fee (\$)	Fees Paid(\$)		
Utility	300	150	500	250		200	100			
Design	200	100	100	50		130	65			
Plant	200	100	300	150		160	80			
Reissue	300	150	500	250		600	300			
Provisional	200	100	0	0		0	0	\$200.00		
2. EXCESS CLAIM FEES  Fee Description Each claim over 20 (including Reissues) Each independent claim over 3 (including Reissues)  Multiple dependent claims  Small Entity Fee (\$) Fee (\$) 25 25 200 100 Multiple dependent claims										
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HP = highest number of independent claims paid for, if greater than 3.  3. APPLICATION SIZE FEE If the specification and drawings exceed 100 sheets of paper (excluding electronically filed sequence or computer listing under 37 CFR 1.52(e)), the application size fee due is \$250 (\$125 for small entity) for each additional 50 sheets or fraction thereof. See 35 U.S.C. 41(a)(1)(G) and 37 CFR 1.16(s).										
Total Sheets   Extra Sheets   Number of each additional 50 or fraction thereof   Fee (\$)   Fee Paid (\$)										
4. OTHER FEE(S)										
Non-English specification, \$130 fee (no small entity discount)  Other (e.g. late filing surcharge):										
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Signature	Write	<u></u>		Registration No. (Attorney/Agent)	3'	7,135	Telephone	312-655-1500		

Date 14 February 2005 L. Friedman Name (Print/Type)

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Patentee:

WALKER

Title:

CHIP SHIELDING SYSTEM AND METHOD

Serial No.:

Filing Date:

14 February 2005

Docket No.

7251/93801

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## CHIP SHIELDING SYSTEM AND METHOD

#### FIELD OF THE INVENTION

The present invention relates to protecting integrated circuit chips from invasive attack through the use of a shield.

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#### BACKGROUND OF THE INVENTION

Security chips are of use to those wanting to protect information, data transmissions or value (typically monetary). These security chips protect data by storing it in secure memory or transmit data securely through the use of cryptography implemented on chip. There are many reasons for using these products including secure banking cards, secure access systems and secure personal identity systems. It is known in the art to protect these chips from invasive attacks whereby criminals and other agents attack the card to try to obtain, change or use secret information on the card.

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One type of attack involves trying to place contacts onto internal chip nodes in order to read internal data traffic. This may be achieved by probing, using fine needles to break through the surface passivation to reach the fine metal tracks. Alternatively focused ion beam (FIB) may be used to deposit pads of metal onto the tracks for subsequent probing or bonding by wires. However it is achieved, measuring the signals on internal chip nodes represents an attack, and if successful this attack may render the chip and entire system on which it is based, insecure.

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Shields to protect a chip from the above attacks exist at present; they are typically divided into two categories, active and passive. Passive shields are simple metal layers over all or part of the circuit and are designed to prevent viewing and probing. Passive shields may be removed by chemical, plasma or other techniques without changing the operation of the circuit. In other words, a passive shield works to deter attackers by making viewing more difficult initially, but will not actively defend itself against removal.

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Active shields may look similar or may look more like a network of lines covering all or part of a circuit. If a line or part of the shield is removed,

severed or short-circuited to another line, the breach is detected and the chip halts some or all functions.

Active shields may still be breached using, for example, the following technique. An active shield line is identified as above the circuit element to be attacked. This shield line is bypassed using the ability of the FIB system previously mentioned. The bypass is in the form of a diversion track added in parallel to the original shield track. The original shield track may now be removed leaving the new bypass to fool the detection circuit. No circuit break is detected.

#### SUMMARY OF THE INVENTION

The present invention, in preferred embodiments thereof, comprises an active shield made in such a way that individual tracks are not visible by any normal microscopy technique. The tracks are preferably present in a layer of semiconductor material. The tracks preferably comprise doped regions separated by semi-insulating regions of either undoped material, or differently doped material. The tracks are doped sufficiently to allow conduction of electronic carriers. Between the tracks, the material, doped or undoped, is depleted of carriers. This region is rendered semi-insulating through the lack of intrinsic or extrinsic carriers, or through the trapping of such carriers. The conductive region is formed into tracks which form part of an active shield as described above. Most preferably, the conductive lines and the insulating regions between them are made in the same way and look identical to all analytical techniques. An attacker therefore does not know where to bypass the active shield lines.

# BRIEF DESCRIPTION OF THE DRAWINGS

The present invention will be understood and appreciated more fully from the following detailed description, taken in conjunction with the drawings in which:

Fig. 1 is a simplified pictorial illustration of an integrated circuit protected by chip shielding, constructed and operative in accordance with a preferred embodiment of the present invention; and

Fig. 2 is a simplified pictorial illustration of a top view of the integrated circuit of Fig. 1.

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#### DETAILED DESCRIPTION OF PREFERRED EMBODIMENTS

The present invention, in preferred embodiments thereof, provides a method to protect a security chip from invasive attacks. Preferably, a layer is added above the layers of the circuit to be protected from attack. The added layer may be made of polycrystalline silicon, as this material is commonly used in the manufacturing cycle of integrated circuits, but may alternatively be made of many other suitable materials. Any material whose conductivity can be materially changed without being visibly different would be a candidate for the material to be used in the added layer. The added layer is typically applied towards the end of the chip manufacturing process, and is applied above the normal circuit interconnect layers. The added layer may also be protected by a passivation layer, as is typically used in such integrated circuits.

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The added layer is preferably implanted with dopants to allow conduction. In one preferred embodiment of the present invention dopants are selectively implanted in tracks corresponding to where the designer wants them placed. Dopants may be implanted in the material by high energy ion bombardment or by any other appropriate method.

In another preferred embodiment of the present invention utilizes either blanket bombardment of the layer with dopant ions or incorporation of the dopants during the growth of the layer. This latter approach will typically be achieved in the case of doped polysilicon, by chemical vapor deposition (CVD) growth using silane gas for silicon growth and boron trichloride gas for dopant species.

However the growth and dopant incorporation is achieved, it must be done in such a way that the incorporated dopant atoms are not active. This means that the dopant atoms are not on designated sites as substitutes for the main material atoms. This means that the dopant atoms are interstitial, or between their normal, substitutional sites. This further means that the dopant atoms do not contribute carriers to conduction processes in the layer. This means that the material, as grown, is semi-insulating and does not conduct.

A further step in the creation of the shield layer is the selective activation of the dopants described above. The selective activation is typically

achieved through an annealing process. This annealing process is effective if the material is heated to a temperature close to (typically, within approximately 100 degrees C of) its melting point. In one preferred embodiment, the doped polysilicon is rapidly brought up to the annealing temperature by irradiation from a pulsed light source. The pulsed light source may be an infrared laser. The laser may be a YAG laser (Yttrium Aluminum Garnet, output wavelength 1064 nm). This laser may be driven in pulsed mode with a q-switch to limit the on-time to several nanoseconds or faster. The high power density during the pulse must be sufficient to anneal the dopants in that region of the material. In addition, the power density during the pulse must not be sufficient to ablate the material or cause damage to active circuit layers.

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Conductive tracks are patterned into the layer by the annealing action. The laser, for example, may be scanned across the surface. The pattern of scanning is immaterial but may be raster scanning or following the semi-random path of a tracks path from start to end, or most efficiently, by alternate direction scanning (boustrephorous scanning) of the surface. The annealing will locally activate the dopants in the tracks required.

The annealing must be such that the conductive tracks are physically similar in all important respects to the semi-insulating material between the tracks. An attacker cannot "see", by normal analytical means, the tracks to be bypassed in an attack.

In certain preferred embodiments of the present invention, in order to further frustrate attackers, the path of the conductive tracks is randomized for each shielded chip produced. This randomization helps stop attackers from trying to characterize a device destructively to find the shield path, then applying the information gained to a pristine device. The additional effort required to randomize the path is preferably implemented in control software and is thus independent of processing hardware.

Randomization in this case may mean annealing to form the conductive tracks using straight lines and 90-degree bends (although it is appreciated that it is not necessary to use straight lines and 90-degree bends), but would be random in how the conductive path connects one contact to another. For

example, in one chip, one may use the simplest path between two points - a straight line. In another chip the same two contacts could be joined by a longer series of meanders, and in other chips by different series of meanders. The point, as stated above, is to prevent a hacker from discovering the path of the shield in one device and using the path information to bypass the shield in all other devices of the same series of chip.

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Even though each chip would have the shield conductive paths in different patterns, the end contacts would preferably be in the same place in each chip, since photolithographic masks, which are difficult to change, define the locations of the contacts. Manufacturing many different copies of photolithographic masks would be extremely expensive. Therefore, the preferred track "writing" process is serial, enabling each chip to be different without incurring the difficulties inherent in changing the photolithographic masks.

It is to be appreciated that the control software could be programmed to route the conductive tracks automatically by driving the laser with randomly added deviations from a simple path from one track end to the other track end. A simpler alternative would be to have a large but fixed number of conductive path patterns, and have a random choice of which pattern to use for each chip.

Reference is now made to Fig. 1, which is a simplified pictorial illustration of an integrated circuit protected by chip shielding, constructed and operative in accordance with a preferred embodiment of the present invention. This figure shows the basic construction of an integrated circuit with a silicon (single crystal) substrate on top of which are constructed gates and other active and passive circuit elements interconnected by networks of (typically) aluminum tracks. As these aluminum tracks are vulnerable to attack a layer of polysilicon is shown above them to illustrate the position of the protective shield layer.

Reference is now made to Fig. 2, which is a simplified pictorial illustration of a top view of the integrated circuit of Fig. 1. This figure shows a top down view of the protective shield layer. The serpentine track illustrates one method, as described above, of writing a serpentine conductive line in this material. As described above, this can be achieved by scanning a pulsed infra-red

laser over the areas to be annealed. The annealing activates the dopants in this region, allowing conduction along the track. The track may be connected to the underlying circuitry using, for example, tungsten plugs as vias.

It is appreciated that various features of the invention which are, for clarity, described in the contexts of separate embodiments may also be provided in combination in a single embodiment. Conversely, various features of the invention which are, for brevity, described in the context of a single embodiment may also be provided separately or in any suitable subcombination.

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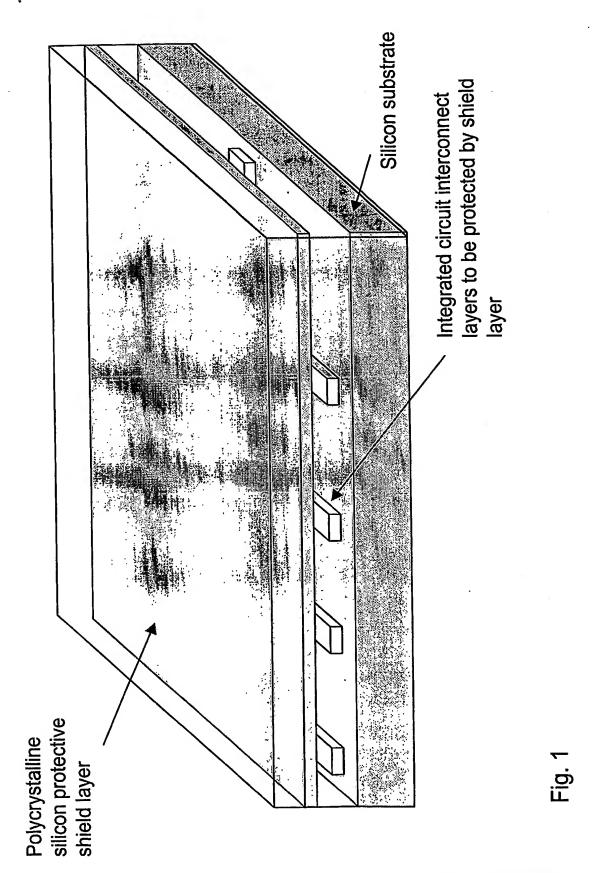
It will be appreciated by persons skilled in the art that the present invention is not limited by what has been particularly shown and described hereinabove. Rather the scope of the invention is defined only by the claims which follow:

#### What is claimed is:

#### **CLAIMS**

Apparatus substantially as described hereinabove.

- 2. Apparatus substantially as shown in the drawings.
- 3. A method substantially as described hereinabove.
- 10 4. A method substantially as shown in the drawings.



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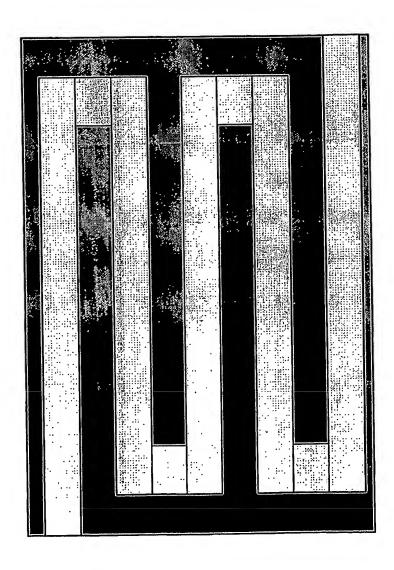


Fig. 2

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